

PHOTOSENSITIVE COMPOSITION

Patent number: JP2096755
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Inventor: NAKAI HIDEYUKI; GOTO SEI; TOMIYASU HIROSHI;
KOBAYASHI YOSHIKO
Applicant: KONISHIROKU PHOTO IND.; MITSUBISHI CHEM IND
Classification:
- **international:** G03F7/004; G03F7/023
- **european:**
Application number: JP19880249398 19881003
Priority number(s): JP19880249398 19881003

Abstract of JP2096755

PURPOSE: To obtain a photosensitive compsn. having superior capacity for forming visible picture by exposure, as well as superior under developability and high sensitivity by constituting the compsn. of 1,2-naphthoquinone-2-diazide-4-sulfonic ester compd. an alkali soluble resin, a halomethyl oxadiazole compd., as a discoloring agent. **CONSTITUTION:** The title compsn. contains 1,2-naphthoquinone-2-diazide-4-sulfonic ester compd., the alkali-soluble resin, the halomethyl oxadiazole compd. which generates free halogen radicals by irradiating with active light rays, and a discoloring agent which changes its tone by the interaction with a photolysis of the halomethyl oxadiazole compd. Suitable alkali-soluble resin is particularly novolak resin and vinyl polymer having structure units having phenolic OH groups in the molecule. A photosensitive planographic printing plate having superior capacity for forming visible picture by exposure, superior under developability, as well as high sensitivity, is obtd. from the above-described compsn.

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Country: JP Japan

Kind: A

Inventor: NAKAI HIDEYUKI;
GOTO SEI;
TOMIYASU HIROSHI;
KOBAYASHI YOSHIKO;Assignee: KONICA CORP
MITSUBISHI KASEI CORP
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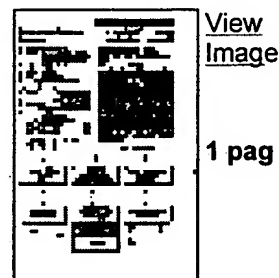
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
Family:

PDF	Publication	Pub. Date	Filed	Title



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	JP02096755A2	1993-06-15	1992-03-24	Photosensitive composition containing 1,2-naphthodione-2-diazido-4-sulfonic acid ester, alkali-soluble resin, halomethyloxadiazole compound and a dye
	JP02096759A2	1990-04-09	1988-10-04	PHOTOSENSITIVE PLANOGRAPHIC PRINTING PLATE
	JP02096755A2	1990-04-09	1988-10-03	PHOTOSENSITIVE COMPOSITION
	EP0362778B1	1999-01-13	1989-10-02	Photosensitive composition
	EP0362778A3	1991-06-12	1989-10-02	Photosensitive composition
	EP0362778A2	1990-04-11	1989-10-02	Photosensitive composition
	DE68928903C0	1999-02-25	1989-10-02	LICHTEMPFLINDLICHE ZUSAMMENSETZUNG
	CA2000111AA	1990-04-03	1989-10-03	PHOTOSENSITIVE COMPOSITION
8 family members shown above				

Other Abstract
Info:

DERABS C90-133305



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